What is claimed is:

1. An apparatus, comprising:

a chamber body at least partially defining a process volume therein;

a pedestal disposed in the process volume, the pedestal comprising a substrate support and a shaft coupled to the chamber body to support the substrate support;

a first electrode disposed in the process volume opposite the pedestal;

a second electrode disposed in the pedestal;

a conductive rod extending through the shaft of the pedestal, the conductive rod coupled to the second electrode;

an RF filter disposed in an enclosure and coupled to the conductive rod, the RF filter comprising:

a first capacitor coupled to the conductive rod and coupled to the enclosure; and

a first inductor coupled to the conductive rod;

a feedthrough box comprising a second inductor and a second capacitor coupled in series;

a cable coupled to the first inductor and coupled to the second inductor;

a power supply coupled to the second electrode through the feedthrough box and the RF filter, the power supply coupled between the second inductor and the second capacitor; and

an RF source coupled to the first electrode,

wherein RF power from the RF source to the first electrode has a frequency of 13.56 MHz.